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| APPLICATION NO. | FILING DATE | FIRST NAMED INVENTOR | ATTORNEY DOCKET NO. | CONFIRMATION NO. |
|-----------------|-------------|----------------------|---------------------|------------------|
| 10/599,208 | 09/22/2006 | Franck Delahaye | RENA-05U1 | 5835 |

59538 7590 07/13/2010
BIOTECH BEACH LAW GROUP, PC
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| EXAMINER |
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ANGADI, MAKI A

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| ART UNIT | PAPER NUMBER |
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1713

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| MAIL DATE | DELIVERY MODE |
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07/13/2010

PAPER

Please find below and/or attached an Office communication concerning this application or proceeding.

The time period for reply, if any, is set in the attached communication.

| | | | |
|------------------------------|--------------------------------------|---|--|
| Office Action Summary | Application No. 10/599,208 | Applicant(s) DELAHAYE, FRANCK | |
| | Examiner MAKI A. ANGADI | Art Unit 1713 | |

-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address --

Period for Reply

A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) OR THIRTY (30) DAYS, WHICHEVER IS LONGER, FROM THE MAILING DATE OF THIS COMMUNICATION.

- Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.
- If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.
- Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).

Status

- 1) ☒ Responsive to communication(s) filed on 02 June 2010.
- 2a) ☐ This action is **FINAL**. 2b) ☒ This action is non-final.
- 3) ☐ Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under *Ex parte Quayle*, 1935 C.D. 11, 453 O.G. 213.

Disposition of Claims

- 4) ☒ Claim(s) 1-27 is/are pending in the application.
- 4a) Of the above claim(s) _____ is/are withdrawn from consideration.
- 5) ☐ Claim(s) _____ is/are allowed.
- 6) ☒ Claim(s) 1-27 is/are rejected.
- 7) ☐ Claim(s) _____ is/are objected to.
- 8) ☐ Claim(s) _____ are subject to restriction and/or election requirement.

Application Papers

- 9) ☒ The specification is objected to by the Examiner.
- 10) ☐ The drawing(s) filed on _____ is/are: a) ☐ accepted or b) ☐ objected to by the Examiner.
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).
- 11) ☐ The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.

Priority under 35 U.S.C. § 119

- 12) ☐ Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).
- a) ☐ All b) ☐ Some * c) ☐ None of:
1. ☐ Certified copies of the priority documents have been received.
 2. ☐ Certified copies of the priority documents have been received in Application No. _____.
 3. ☐ Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).

* See the attached detailed Office action for a list of the certified copies not received.

Attachment(s)

- | | |
|---|---|
| 1) <input type="checkbox"/> Notice of References Cited (PTO-892) | 4) <input type="checkbox"/> Interview Summary (PTO-413) Paper No(s)/Mail Date. _____ |
| 2) <input type="checkbox"/> Notice of Draftperson's Patent Drawing Review (PTO-948) | 5) <input type="checkbox"/> Notice of Informal Patent Application |
| 3) <input checked="" type="checkbox"/> Information Disclosure Statement(s) (PTO/SB/08) Paper No(s)/Mail Date <u>6/2/2010</u> . | 6) <input type="checkbox"/> Other: _____ |

DETAILED ACTION

Continued Examination Under 37 CFR 1.114

1. A request for continued examination under 37 CFR 1.114, including the fee set forth in 37 CFR 1.17(e), was filed in this application after final rejection. Since this application is eligible for continued examination under 37 CFR 1.114, and the fee set forth in 37 CFR 1.17(e) has been timely paid, the finality of the previous Office action has been withdrawn pursuant to 37 CFR 1.114. Applicant's submission filed on 6/2/2010 has been entered.

Specification Objections

2. The disclosure is objected to because of the following informalities:

Applicant's specification is not in the correct format. Applicants are advised to present the specification in the correct format with following subtitles. Please refer to the MPEP for additional information in Chapter 6 and in particular, 37 CFR 1.51. No new matter may be introduced in the introduction of these new subtitles. Appropriate correction is required.

Content of Specification

- (a) Title of the Invention: See 37 CFR 1.72(a) and MPEP § 606. The title of the invention should be placed at the top of the first page of the specification unless the title is provided in an application data sheet. The title of the invention should be brief but technically accurate and descriptive, preferably from two to seven words may not contain more than 500 characters.
- (b) Cross-References to Related Applications: See 37 CFR 1.78 and MPEP § 201.11.
- (c) Statement Regarding Federally Sponsored Research and Development: See MPEP § 310.

- (d) The Names Of The Parties To A Joint Research Agreement: See 37 CFR 1.71(g).
- (e) Incorporation-By-Reference Of Material Submitted On a Compact Disc: The specification is required to include an incorporation-by-reference of electronic documents that are to become part of the permanent United States Patent and Trademark Office records in the file of a patent application. See 37 CFR 1.52(e) and MPEP § 608.05. Computer program listings (37 CFR 1.96(c)), "Sequence Listings" (37 CFR 1.821(c)), and tables having more than 50 pages of text were permitted as electronic documents on compact discs beginning on September 8, 2000.
- (f) Background of the Invention: See MPEP § 608.01(c). The specification should set forth the Background of the Invention in two parts:
 - (1) Field of the Invention: A statement of the field of art to which the invention pertains. This statement may include a paraphrasing of the applicable U.S. patent classification definitions of the subject matter of the claimed invention. This item may also be titled "Technical Field."
 - (2) Description of the Related Art including information disclosed under 37 CFR 1.97 and 37 CFR 1.98: A description of the related art known to the applicant and including, if applicable, references to specific related art and problems involved in the prior art which are solved by the applicant's invention. This item may also be titled "Background Art."
- (g) Brief Summary of the Invention: See MPEP § 608.01(d). A brief summary or general statement of the invention as set forth in 37 CFR 1.73. The summary is separate and distinct from the abstract and is directed toward the invention rather than the disclosure as a whole. The summary may point out the advantages of the invention or how it solves problems previously existent in the prior art (and preferably indicated in the Background of the Invention). In chemical cases it should point out in general terms the utility of the invention. If possible, the nature and gist of the invention or the inventive concept should be set forth. Objects of the invention should be treated briefly and only to the extent that they contribute to an understanding of the invention.
- (h) Brief Description of the Several Views of the Drawing(s): See MPEP § 608.01(f). A reference to and brief description of the drawing(s) as set forth in 37 CFR 1.74.

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- (i) Detailed Description of the Invention: See MPEP § 608.01(g). A description of the preferred embodiment(s) of the invention as required in 37 CFR 1.71. The description should be as short and specific as is necessary to describe the invention adequately and accurately. Where elements or groups of elements, compounds, and processes, which are conventional and generally widely known in the field of the invention described and their exact nature or type is not necessary for an understanding and use of the invention by a person skilled in the art, they should not be described in detail. However, where particularly complicated subject matter is involved or where the elements, compounds, or processes may not be commonly or widely known in the field, the specification should refer to another patent or readily available publication which adequately describes the subject matter.
- (j) Claim or Claims: See 37 CFR 1.75 and MPEP § 608.01(m). The claim or claims must commence on separate sheet or electronic page (37 CFR 1.52(b)(3)). Where a claim sets forth a plurality of elements or steps, each element or step of the claim should be separated by a line indentation. There may be plural indentations to further segregate subcombinations or related steps. See 37 CFR 1.75 and MPEP § 608.01(i)-(p).
- (k) Abstract of the Disclosure: See MPEP § 608.01(f). A brief narrative of the disclosure as a whole in a single paragraph of 150 words or less commencing on a separate sheet following the claims. In an international application which has entered the national stage (37 CFR 1.491(b)), the applicant need not submit an abstract commencing on a separate sheet if an abstract was published with the international application under PCT Article 21. The abstract that appears on the cover page of the pamphlet published by the International Bureau (IB) of the World Intellectual Property Organization (WIPO) is the abstract that will be used by the USPTO. See MPEP § 1893.03(e).
- (l) Sequence Listing. See 37 CFR 1.821-1.825 and MPEP §§ 2421-2431. The requirement for a sequence listing applies to all sequences disclosed in a given application, whether the sequences are claimed or not. See MPEP § 2421.02.

Claim Rejections - 35 USC § 103

3. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and

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the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negated by the manner in which the invention was made.

4. Claims 1-27 are rejected under 35 U.S.C. 103(a) as being unpatentable over Hiraishi et al. (US 6,506,260).

As to claims 1-6, 10-15, 17, 19-23, 26 and 27, in a method of cleaning photovoltaic module (solar cells), Hiraishi discloses treating one side of silicon wafers in a liquid bath, characterized in that the under side of the silicon wafers is treated in the liquid bath without the top side previously having been protected or masked. The silicon wafers may be processed or cleaned continuously (col.7, lines 32-33) using apparatus illustrated in Fig.1 (col.6, lines 42-45) continuously in a once-through process. The undersides of the silicon wafers may be lowered into the liquid bath. The silicon wafers may be conveyed horizontally through rollers (15a, Fig.1) through the treatment liquid located in the liquid bath. The liquid bath used is a tank whose peripheral edge may be lower than the level of the treatment liquid. The edges of the silicon wafers may be also treated. The production line may comprise a multiplicity of conveyor rolls. The conveyor rolls may be in each case arranged on axle elements. See abstract, col. 1, lines 19-23, 62-63, and Fig. 1 and its description in specification. Hiraishi does not explicitly disclose that the wafer not to be treated is always positioned above the liquid. However, Hiraishi discloses the level of water in the cleaning bath can be controlled (col.7, lines 5-12). Therefore, one who is skilled in the art should be

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able to control the water level so that the wafers which are not to be treated are positioned above the liquid.

As to claims 7-9, 16 and 18, 24-25, Hiraishi discloses treating one side of silicon wafers in a liquid bath, characterized in that the under side of the silicon wafers is treated in the liquid bath without the top side previously having been protected or masked. The silicon wafers may be processed continuously in a once-through process. The undersides of the silicon wafers may be lowered into the liquid bath. The silicon wafers may be conveyed horizontally through the treatment liquid located in the liquid bath. The liquid bath used is a tank whose peripheral edge may be lower than the level of the treatment liquid. The edges of the silicon wafers may be also treated. The production line may comprise a multiplicity of conveyor rolls. The conveyor rolls may be in each case arranged on axle elements. See abstract, col. 1, lines 19-23, 62-63, and Fig. 1 and its description in spec.

Hiraishi discloses treating (cleaning) silicon wafers in a liquid bath. Since the cleaning and etching may use the same process and system with different chemicals e.g. pure water or alternatively, acetone, alcohol, Freon or oxidizing acid solution or hydrochloric acid solution (col.9, lines 18-20) in treatment, therefore, it would have been obvious to one with ordinary skill in the art at the time of the invention was made to vary chemical composition for treatment so as to etch the silicon wafers if the etching is required for the product.

The above cited claims differ from the prior art by specifying well-known features (such as commonly used etchants in claims 7 and 8); use additives for binding the gas formed during the etching so as to avoid or suppress gas bubbles in claims 9 and 18; encapsulate the axle element for the protection in claim 16) to the art of wet cleaning and etching, the examiner takes official notice. A person having ordinary skill in the art would have found it obvious to modify the prior art by adding any of same well-known features to the same in order to provide efficient cleaning or etching with a reasonable expectation of success.

Response to Arguments

5. Applicant's arguments filed on 6/2/2010 have been fully considered but they are not persuasive.

With respect to claims 1 and 10, applicants arguments on pages 10-22 of the reply asserting that the prior art of Hiraishi does not teach that the top side of the wafers which are not to be treated are always positioned above the liquid are not convincing. Hiraishi disclose in Fig.1 a cleaning apparatus wherein one who is skilled in the art should be able to control the water level so that the wafers which are not to be treated are positioned above the liquid. It is noted that the level and type of cleaning liquid, position of wafers, and oxidizing agents used are adjustable parameters which are optimized for the best results of cleaning or etching.

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to MAKI A. ANGADI whose telephone number is (571)272-8213. The examiner can normally be reached on 8 AM to 4.30 PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Nadine G. Norton can be reached on 571-272-1465. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

/Maki A Angadi/
Examiner, Art Unit 1713

/Lan Vinh/
Primary Examiner, AU 1713